

ABSTRACT

A method for treating an implant surface intended for implantation into bone wherein a microroughness having pores and peaks having a pore diameter of $\leq 1 \mu\text{m}$, a pore depth of $\leq 500 \text{ nm}$, and a peak width, at half the pore depth, of from 15 to 150% of the pore diameter is provided. Also provided is an implant having a surface with the above characteristics.